

SHIGA7.054APC

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[APC Rec'd PCT] 13 AUG 2006

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

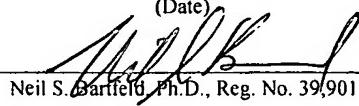
Applicant : Ogata et al.
Appl. No. : U.S. National Phase of
PCT/JP2005/001228
Filed : Herewith
For : POLYMER COMPOUND,
PHOTORESIST COMPOSITION
INCLUDING THE POLYMER
COMPOUND, AND RESIST
PATTERN FORMATION
METHOD
Examiner : Unassigned
Group Art Unit : Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence and all
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Alexandria, VA 22313-1450, on

August 16, 2006

(Date)


Neil S. Garfield, Ph.D., Reg. No. 39,901

PRELIMINARY AMENDMENT

Mail Stop PCT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Prior to examination of the above-referenced application, please enter the following
amendments:

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims begin on page 3 of this paper.

Remarks begin on page 8 of this paper.